**PATENT APPLICATION**Attorney Docket No.: 105875

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**AMENDMENT TRANSMITTAL**

In re the Application of

Masaru MITSUI et al.  
Application No.: 09/509,472

Group Art Unit: 1752  
Examiner: Y. Clarke

Filed: April 21, 2000

For: PHOTOMASK BLANK, PHOTOMASK, METHODS OF MANUFACTURING THE SAME AND  
METHOD OF FORMING MICROPATTERN

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

Transmitted herewith is an Amendment in the above-identified application.

- ☐ Entitlement to small entity status is hereby asserted.  
☐ Small entity status of this application has been established.

The filing fee has been calculated as shown below:

	(Column 1)	(Column 2)	(Column 3)	SMALL ENTITY			OTHER THAN A SMALL ENTITY	
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NO. PREVIOUSLY PAID FOR	PRESENT EXTRA	RATE	ADD'L FEE	OR	RATE	ADD'L FEE
TOTAL CLAIMS	*30 MINUS	**26	=4	x 9	\$		x 18	\$72
INDEP CLAIMS	*5 MINUS	***5	=0	x 42	\$		x 84	\$
<input type="checkbox"/> FIRST PRESENTATION OF MULTIPLE DEP. CLAIM				+ 140	\$	OR	+280	\$
					\$			\$72

- \* If the entry in Column 1 is less than the entry in Column 2, write "0" in Column 3.  
\*\* If the "Highest Number Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.  
\*\*\* If the "Highest Number Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.

The "Highest Number Previously Paid For" in this space (Total or Independent) is the highest number found from the equivalent box in Column 1 of a prior Amendment or the number of claims originally filed.

- ☒ Check No. 127081 in the amount of \$72.00 is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.

DEPOSIT ACCOUNT USE  
AUTHORIZATION  
Please grant any extension  
necessary for entry;  
Charge any fee due to our  
Deposit Account No. 15-0461

Respectfully submitted,

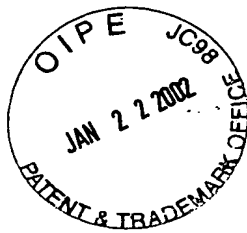
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JAN 30 2002  
TC 1700

JAO:JSA:DML/rxg  
Date: January 22, 2002



**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Masaru MITSUI et al.

Group Art Unit: 1752

Application No.: 09/509,472

Examiner: Y. Clarke

Filed: April 21, 2000

Docket No.: 105875

For: PHOTOMASK BLANK, PHOTOMASK, METHODS OF MANUFACTURING THE SAME AND METHOD OF FORMING MICROPATTERN

**AMENDMENT**

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed August 22, 2001, please amend the above-identified application as follows:

**IN THE SPECIFICATION:**

Page 16, lines 11-23, delete current paragraph and insert therefor:

With the photomask blank 1 pertaining to Example 1 shown in Figure 1, a quartz glass substrate measuring 5 inches  $\times$  5 inches  $\times$  0.09 inch and whose main surface and end face had undergone precision polishing was used as the transparent substrate 2. Over this transparent substrate 2 were formed a chromium nitride (CrN) film (Cr: 80 atomic%, N: 20 atomic% (hereafter called at%); film thickness 150 Å) as a first shading film (light-shielding film, opaque film, non-transmitting film) 3, a chromium carbide (CrC) film (Cr: 94 at%, C: 6 at%; film thickness: 600 Å) as a second shading film (light-shielding film, opaque film, non-transmitting film) 4, and a chromium oxynitride (CrON) film (Cr: 30 at%, O: 45 at%, N: 25 at%; film thickness: 250 Å) as an anti-reflective film 5.

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